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Nahee Park, Ph.D. has been an application engineer at KLA Corp. and has researched the imaging-based overlay metrology in advanced device node circuits while collaborating with SK Hynix, Samsung electronics, Micron technology, Intel Corp., and IBM Corp., since September 2020. She received a Ph.D degree in Science from Sungkyunkwan University (SKKU), South Korea in August 2020 where she studied semiconductor device physics during integrated M.S.-Ph.D course. Her current research interest is optical metrology development for state-of-art device process control in the semiconductor industry.